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[TSMC2003-0899]

FACSIMILE TRANSMITTAL SHEET

In re application of: **Huang-Ming Chen et al.**

Examiner: **Karla A. Moore**

Serial No.: **10/765,808**

Group Art Unit: **1792**

Filed: **01/27/2004**

Confirmation No.: **2454**

For: METHOD AND APPARATUS FOR BACKSIDE POLYMER REDUCTION IN DRY-ETCH PROCESS

To: Examiner Karla A. Moore
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

FACSIMILE NUMBER: 571-273-1440

CONFIRMATION

TELEPHONE:

FROM: Mark J. Marcelli

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DATE: August 7, 2008

TOTAL # OF PAGES:
(INCLUDING COVERSHEET)

MESSAGE: Pursuant to our telephone conversation of August 7, 2008, please call to discuss the proposed amendment to (rejected) claim 8.

Mark J. Marcelli

NOTE: Original will not follow

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1 8. (Currently Amended) A plasma etching apparatus comprising a chuck for
2 retaining a substrate and a focus ring set, at least one of said chuck and said focus ring
3 set formed of a material that includes oxygen therein such that said oxygen is released
4 when an etching operation is carried out, said focus ring set including an upper focus
5 ring that laterally surrounds said chuck and a lower focus ring disposed completely
6 below said upper focus ring and directly underneath a peripheral portion of said chuck
7 substrate.